

## Supporting Information

# Effects of Solution Processable CuI Thin Films with Al<sub>2</sub>O<sub>3</sub>-Based Sandwiched Architecture for High-Performance p-Type Transistor Applications

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S1. Ellipsometry spectra of the Al<sub>2</sub>O<sub>3</sub> interfacial layers.

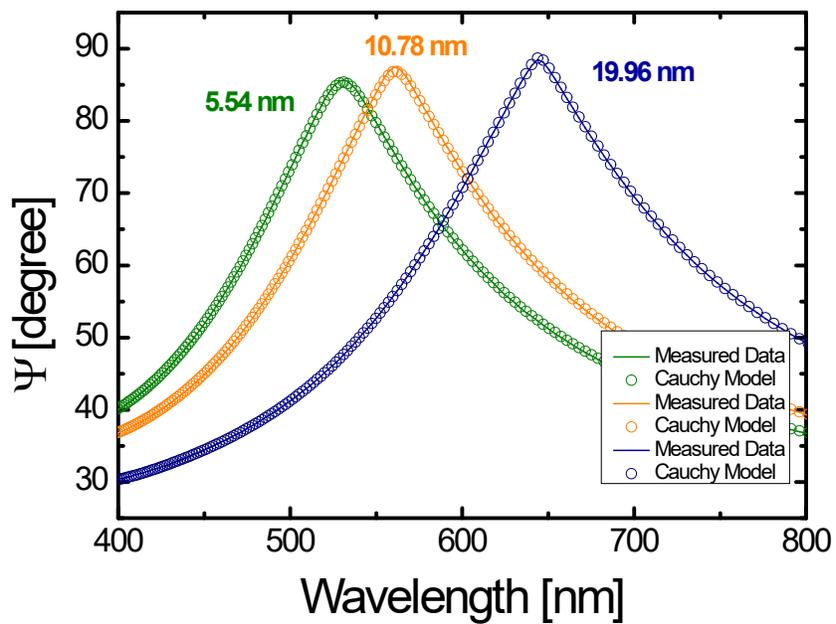


Figure S1. Thicknesses of the Al<sub>2</sub>O<sub>3</sub> interfacial layers measured by spectroscopic ellipsometry.

S2. Transfer curves of the CuI TFTs without  $\text{Al}_2\text{O}_3$  passivation layer.

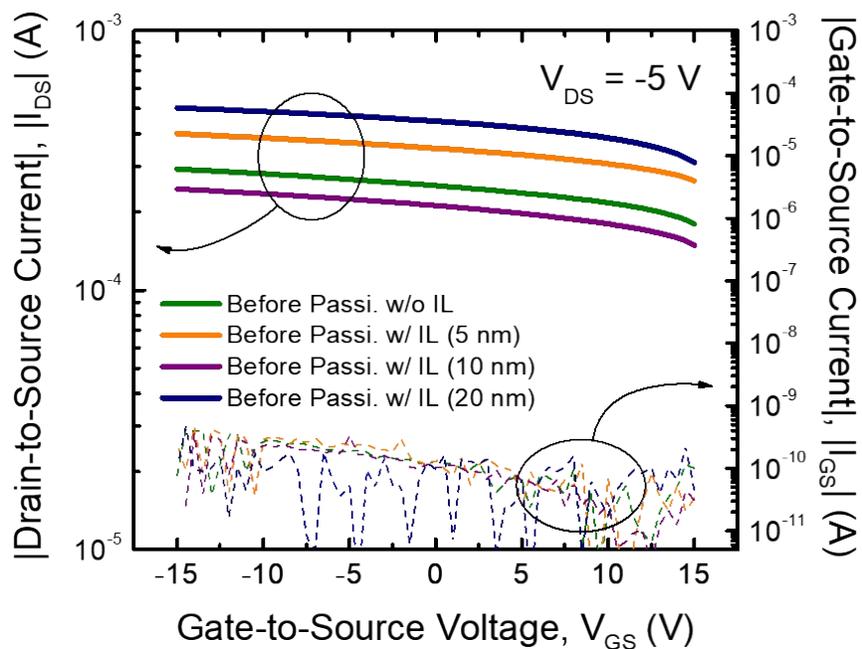


Figure S2. Transfer curves of the CuI TFTs with the  $\text{Al}_2\text{O}_3$  interfacial layers having various thicknesses of 0 to 20 nm without passivation layer.

S3. Dual-sweep transfer curves of the CuI TFTs with various Al<sub>2</sub>O<sub>3</sub>-based sandwiched architectures.

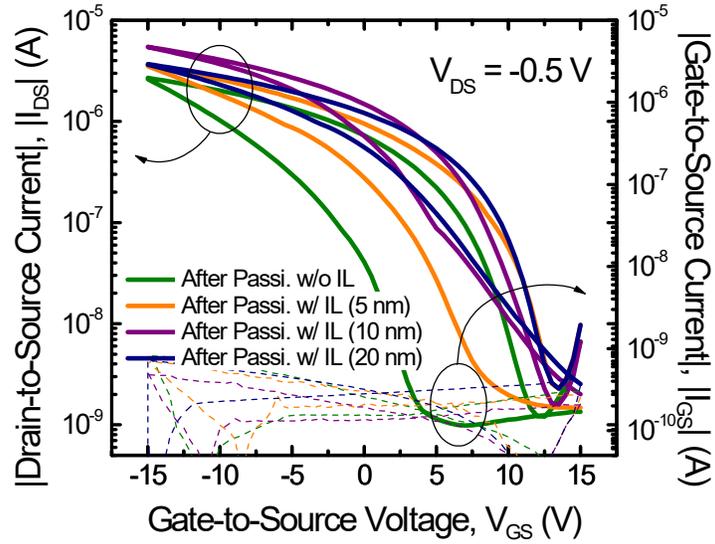


Figure S3. Dual-sweep transfer curves of the CuI TFTs with various Al<sub>2</sub>O<sub>3</sub>-based sandwiched architectures having thicknesses of 5 to 20 nm.

S4. AFM topographies of various gate dielectric stacks.

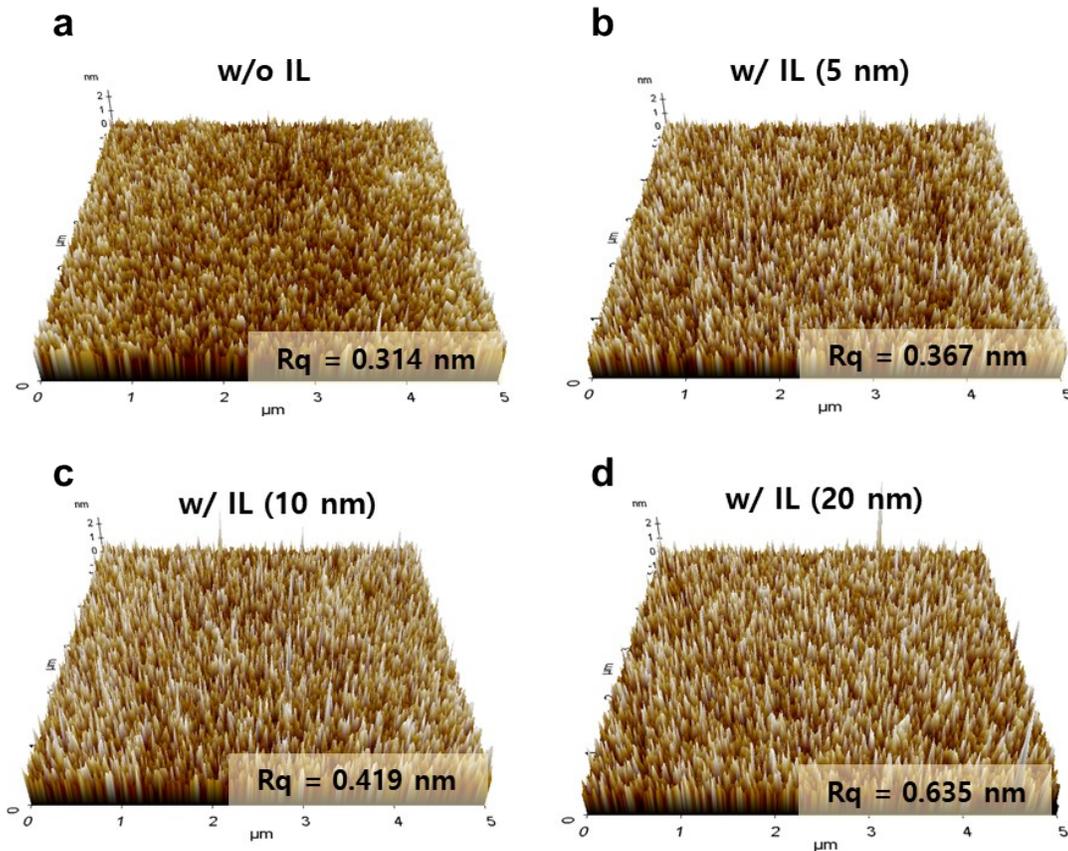


Figure S4. AFM topographies of various gate dielectric stacks (a) without the  $\text{Al}_2\text{O}_3$  interfacial layer and with the  $\text{Al}_2\text{O}_3$  interfacial layer having thicknesses of (b) 5 nm, (c) 10 nm, and (d) 20 nm.

S5. SEM images of the CuI thin film with the Al<sub>2</sub>O<sub>3</sub>-based sandwiched architecture.

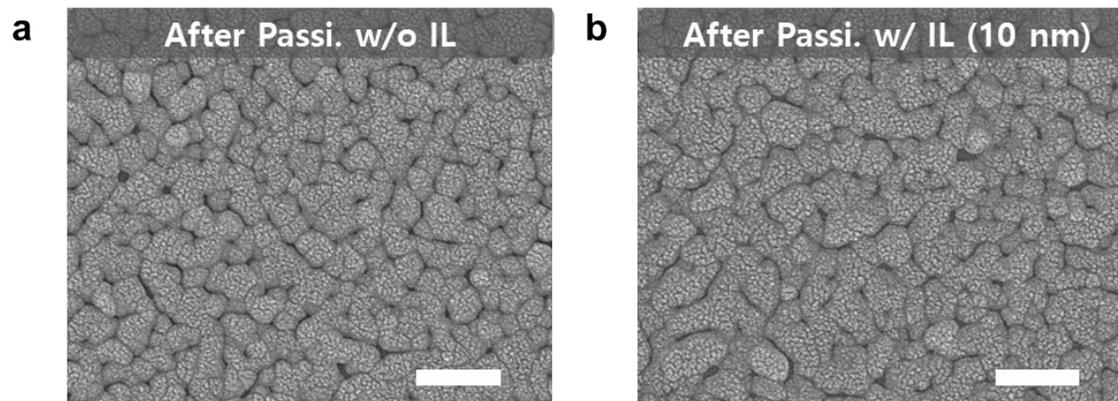


Figure S5. SEM images of the CuI thin film with the Al<sub>2</sub>O<sub>3</sub>-based sandwiched architecture (a) without Al<sub>2</sub>O<sub>3</sub> interfacial layer and (b) with 10 nm-thick-Al<sub>2</sub>O<sub>3</sub> interfacial layer. The scale bar represents 100 nm.

S6. Output curves of the CuI TFTs with Al<sub>2</sub>O<sub>3</sub>-based sandwiched architecture.

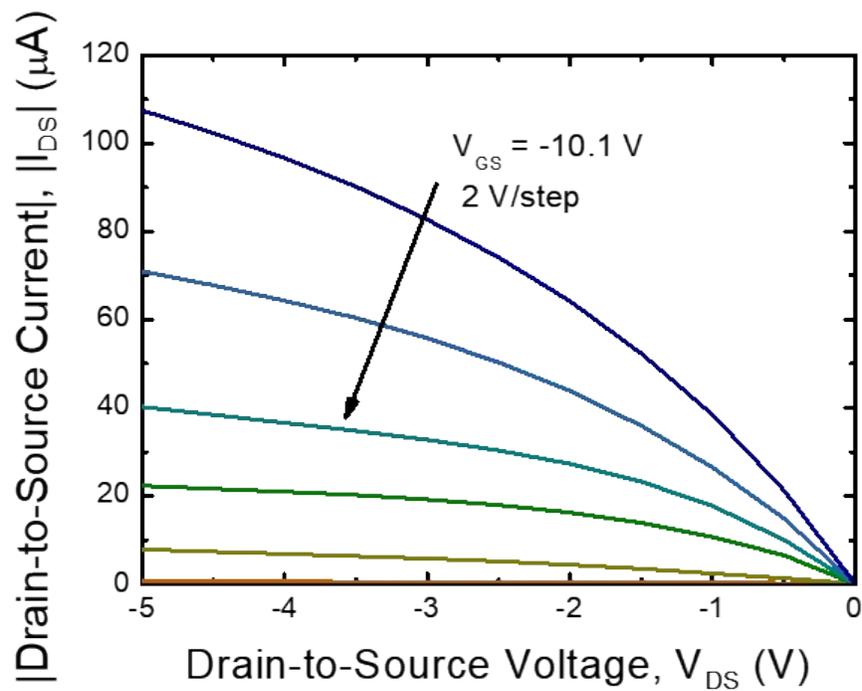


Figure S6. Output curves of the CuI TFTs with Al<sub>2</sub>O<sub>3</sub>-based sandwiched architecture.

S7. Transfer curves ( $\sqrt{|I_{DS}|}$  versus  $V_{GS}$ ) of the CuI TFTs.

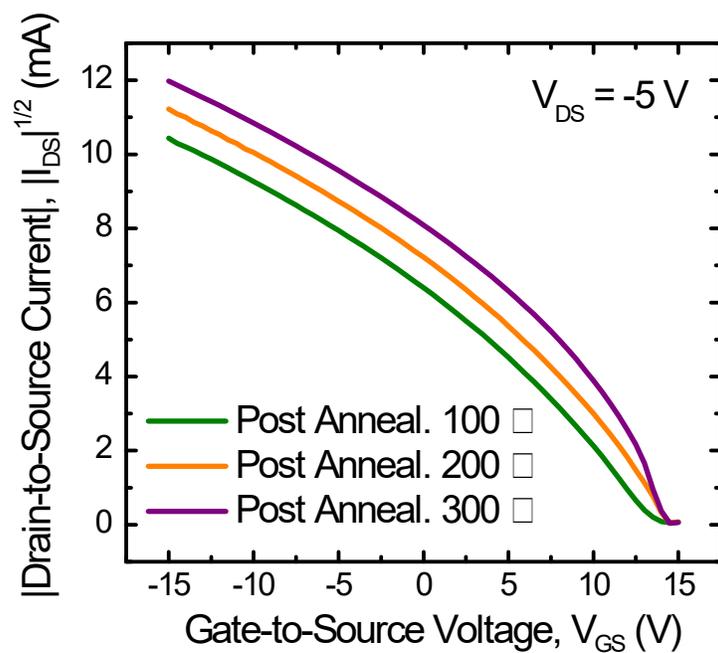


Figure S7. Transfer curves ( $\sqrt{|I_{DS}|}$  versus  $V_{GS}$ ) of the CuI TFTs after post annealing process.

S8. Transfer curves of the CuI TFTs before and after thermal annealing.

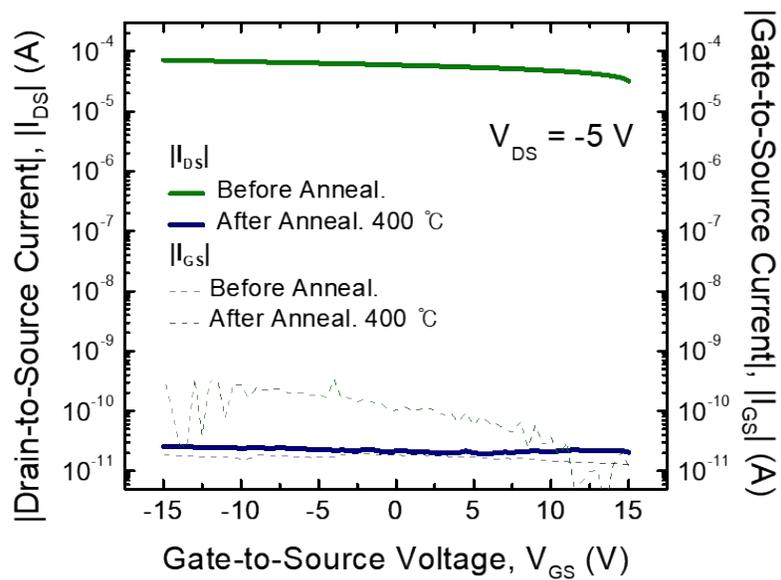


Figure S8. Transfer curves of the CuI TFTs before and after thermal annealing at a temperature of 400 °C.